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U.S. UTILITY Patent Application

PATENT NUMBER and
ISSUE DATE

APPL NUM 10073223	FILING DATE 02/13/2002	CLASS 430	SUBCLASS 270.1	CAU 1752	EXAMINER Lee J-J
**APPLICANTS: Nishi Tsunehiro; Nakashima Mutsuo; Tachibana Seiichiro; Funatsu Kenji;					
**CONTINUING DATA VERIFIED:					
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** FOREIGN APPLICATIONS VERIFIED: JAPAN 2001-037247 02/14/2001 JAPAN 2001-037262 02/14/2001 JAPAN 2001-037271 02/14/2001					
PG-PUB <input type="checkbox"/>		DO NOT PUBLISH <input type="checkbox"/>		RESCIND <input type="checkbox"/>	
Foreign priority claimed <input type="checkbox"/> yes <input type="checkbox"/> no 35 USC 119 conditions met <input type="checkbox"/> yes <input type="checkbox"/> no Verified and Acknowledged Examiners's initials				ATTORNEY DOCKET NO KOJIM-446	
TITLE : Polymer, resist composition and patterning process					
U.S. DEPT. OF COMM./PAT. & TM.-PTO-435L (Rev. 12-94)					

NOTICE OF ALLOWANCE MAILED		CLAIMS ALLOWED		
ISSUE FEE		Assistant Examiner	Total Claims	Print Claim for O.G.
Amount Due	Date Paid			
<input type="checkbox"/> TERMINAL DISCLAIMER		Primary Examiner	DRAWING	
			Sheets Drwg.	Figs. Drwg.
				Applicant Examiner
		PREPARED FOR ISSUE		
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